claimed elements in isolation. Rather, "[a]nticipation requires the presence in a single prior art reference disclosure of each and every element of the claimed invention, arranged as in the claim." Lindemann Maschinenfabrik GmbH v. American Hoist & Derrick Co., 730 F.2d 1452, 221 USPQ 481,485 (Fed. Cir. 1984). Thus, even if the prior art reference includes all of the elements that are claimed, if the arrangement of the claimed elements is different from the arrangement of the prior art elements, anticipation will not be present. Further, anticipation will not be found when the prior art is lacking or missing a specific feature or structure of the claimed invention. Finally, regarding inherency, "[i]nherency...may not be established by probabilities or possibilities. The mere fact that a certain thing may result from a given set of circumstances is not sufficient." In re Oelrich, 666 F.2d 578, 581, 212 USPQ 323, 326 (C.C.P.A. 1981). That is, a missing element or function must necessarily result from the prior art reference. Furthermore, regarding teaching or disclosing, the description must enable a person with ordinary skill in the art not only to comprehend the invention, but also to make it. In re Wilder, 429 F. 2d 477, 166 USPQ 545 (C.C.P.A. 1970).

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Regarding Claim 1

The Examiner stated, regarding Claim 1, that Seabaugh, in figures 12-13 discloses diodes including an n-collector region 218 formed on a diode region, wherein each diode region has an independently [selectable] depth including an ion-implanted portion 216, the n-collector having a contact region opposite the diode region, each diode having a depth, and including means for electrical isolation each diode. The Examiner further stated that the contact surface in Seabaugh ('860) is co-planar with the other n-collector regions 220, referring to fig. 13.

The Applicant has thoroughly reviewed the patent by Seabaugh ('860), and could find no basis for the Examiner's assertion that Seabaugh ('860) discloses diode regions having independently selectable depth, either in terms of ion implantation depth or physical depth. The Applicant has arrived at this conclusion not only after a thorough review of this patent, but also after a word search of the text of the patent using keywords including "independent," which yielded one occurrence at column 3, line 53-54; "doped," which yielded five occurrences in the paragraph beginning at column 5, line 9 and one occurrences in the paragraph beginning at column 5, line 9 and three occurrences in the

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paragraph beginning at column 5, line 43; and "etch," which yielded three occurrences in the paragraph beginning at column 5, line 43. No where in the patent did the Applicant find any combination of these terms or of any similar terms that would indicate that this feature is taught by Seabaugh ('860). Rather, the diodes of Seabaugh ('860) are fabricated by ordinary semiconductor fabrication means. The focus of the invention of Seabaugh ('860) is the provision of muli-finger (either base or emitter) transistors that provide a set of resonant tunneling diodes that each switch at a different voltage. Contrary to the Examiner's assertion, the invention of Seabaugh ('860) does not contain any mention of ion implantation. This is different from the present invention, which provides a plurality of diodes, each having an independently tailorable current-voltage characteristic, and where the mechanism for providing this independence is either an independently selectable ion implant depth or an independently selectable physical depth, as depicted clearly in FIGs. 2 and 3 (respectively) of the present application.

Although the present invention may be used to achieve the same goal as that of the invention of Seabaugh ('860), it does so in a very different manner that is not anticipated by Seabaugh ('860). By not including additional "fingers," the present invention allows for a much more compact solution, thereby conserving circuit board "real estate."

Because Seabaugh ('860) does not teach this feature of the present invention, either expressly or inherently, the Seabaugh ('860) fails to provide (1) a single reference (2) that teaches or enables (3) each of the claimed elements (as arranged in the claim) (4) either expressly or inherently and (5) as interpreted by one of ordinary skill in the art. Thus, the Applicant respectfully requests that the Examiner withdraw this rejection of Claim 1.

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Regarding Claim 2

Regarding Claim 2, the Examiner stated that Seabaugh ('860) further discloses the diode region being formed as a resonant tunneling diode region, referring to the Abstract.

For reasons set forth above, the Applicant asserts that Seabaugh ('860) fails to teach each and every feature of the present invention, arranged as claimed in Claim 1, which the Applicant believes is allowable on that basis. Moreover, because Claim 2